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CERTIFICATE OF MAILING

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Rebecca A. Baumark

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PATENT

Attorney Docket No. NTI-024

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application

PATENT APPLICATION

Inventor(s): Fang-Cheng Chang et al.

Art Unit: 2623

Application No.: 09/941,453

Examiner: J. Mancuso

Filed: 08/28/2001

Title System And Method For Identifying Dummy
Features On A Mask Layer

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. §1.97

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Listed below or on an attached Form PTO-1449 is information known to applicant(s). A copy of each listed publication and U.S. and foreign patent, except for pending U.S. applications, is being submitted herewith, along with a concise explanation of information in a foreign language, if any, pursuant to 37 C.F.R. §1.97-1.98.

Applicants respectfully request that the listed information be considered by the Examiner and be made of record in the above-identified application. If form PTO-1449 is enclosed, the Examiner is requested to initial and return it in accordance with MPEP § 609.

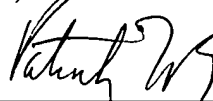
This statement is not intended to represent that a search has been made or that the information cited in the statement is, or is considered to be, material to patentability as defined in 37 C.F.R. § 1.56.

- ☒ This statement qualifies under 37 C.F.R. § 1.97, subsection (b) because (check all that apply):
- ☐ (1) It is being filed within 3 months of the application filing date and is other than a continued prosecution application under § 1.53(d)
-- OR --
 - ☐ (2) It is being filed within 3 months of entry of a national stage
-- OR --
 - ☒ (3) It is being filed before the mail date of the first Office Action on the merits.
-- OR --
 - ☐ (4) It is being filed before the mailing of a first Office Action after the filing of a request for continued examination under § 1.114
- ☐ 37 C.F.R. § 1.97(c). If this statement is being filed after the period specified in § 1.97(b), but before the mailing date of the earlier of a final office action under § 1.113, a notice of allowance under § 1.311, or an action that otherwise closes prosecution in the application, then:
- ☐ a certification as specified in § 1.97(e) is provided below; **or**
 - ☐ a fee of \$180.00 as set forth in § 1.17(p) is authorized below, enclosed, or included with the payment of other papers filed together with this statement.
- ☐ 37 C.F.R. § 1.97(d). If this statement is being filed after the period specified in § 1.97(c), but on or before payment of the issue fee, then:
- A. a certification as specified in § 1.97(e) is completed below; **and**
 - B. a fee of \$180.00 as set forth in § 1.17(p) is authorized below, enclosed, or included with the payment of other papers filed together with this statement.
- ☒ **Fee Authorization.** The Commissioner is hereby authorized to charge any additional fees or credit any overpayment associated with this communication to Deposit Account No. 50-0574 (Docket No. NTI-024).

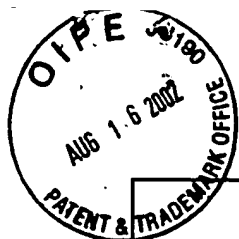
Respectfully submitted,

BEVER, HOFFMAN & HARMS, LLP

Dated: Aug 12, 2002

By:  Reg No. 33834
Jeanette S. Harms, Reg. No. 35,537

Telephone: (408) 451-5907
Customer No. 29477

SHEET 1 of 3

INFORMATION DISCLOSURE CITATION PTO-1449	Atty. Docket No.	Serial No.
	NTI-024	09/941,453-6364
	Applicant	
	CHANG, Fang-Cheng	
	Filing Date	Group
	8/28/2001	Not Yet Assigned

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	6,016,357	1/18/2000	Neary, et al.	382	144	6/16/1997
	6,023,328	2/8/2000	Pierrat	356	237.4	2/23/1998
	6,076,465	6/20/2000	Vacca, et al.	101	481	9/19/1997
	6,091,845	7/18/2000	Pierrat, et al.	382	144	2/24/1998
	6,272,236	8/7/2001	Pierrat, et al.	382	144	7/18/2000
	6,334,209 B1	12/25/2001	Hashimoto, et al.	716	21	9/2/1999
	2002/0019729 A1	2/14/2002	Chang, et al.	703	6	8/7/1998

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SHEET 2 of 3

INFORMATION DISCLOSURE CITATION PTO-1449	Atty. Docket No.	Serial No.
	NTI-024	09/941,453-6364
	Applicant	
	CHANG, Fang-Cheng	
	Filing Date	Group
	8/28/2001	Not Yet Assigned

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
	WO 97/13370	4/10/1997	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 98/20327	5/14/1998	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 98/45685	10/15/1998	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 99/38002	7/29/1999	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 99/56113	11/4/1999	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 99/59200	11/18/1999	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 99/67626	12/29/1999	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 99/14706 A2/A3	3/25/1999	WO			<input type="checkbox"/>	<input type="checkbox"/>

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SHEET 3 of 3

INFORMATION DISCLOSURE CITATION PTO-1449		Atty. Docket No. NTI-024 Applicant CHANG, Fang-Cheng Filing Date 8/28/2001	Serial No. 09/941,453-6364 Group Not Yet Assigned
RECEIVED AUG 20 2002 Technology Center 2600			
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)			
EXAMINER'S INITIALS	CITATION		
	Spence, C., et al., "Detection of 60(degree) Phase Defects on Alternating PSMs", Advanced Micro Devices, KLA-Tencor, DuPont RTC (2 pages).		
	Ogawa, K., et al., "Phase Defect Inspection by Differential Interference", Lasertec Corporation (12 pages).		
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	Fiekowsky, P., "The End of Thresholds: Subwavelength Optical Linewidth Measurement Using the Flux-Area Technique", Automated Visual Inspection (6 pages).		
	Watanabe, H., et al., "Detection and Printability of Shifter Defects in Phase-Shifting Masks", Japanese Journal of Applied Physics, Vol. 30, No. 11B, pp. 3016-3020, November 1991.		
	Hosono, K., et al., "A Novel Architecture for High Speed Dual Image Generation of Pattern Data for Phase Shifting Reticle Inspection", SPIE - Integrated Circuit Metrology, Inspection, and Process Control VI, Vol. 1673, pp. 229-235 (1992).		
	Ohtsuka, H., et al., "Evaluation of Repair Phase and Size Tolerance for a Phase-Shift Mask", J. Vac. Sci. Technol. B, Vol. 11, No. 6, pp. 2665-2668, November/December 1993.		
	Reynolds, J., "Elusive Mask Defects: Reflectivity Variations", Solid State Technology, pp. 75-76, March 1995.		
	Kusunose, H., et al., "Direct Phase-Shift Measurement with Transmitted Deep-UV Illumination", SPIE, Vol. 2793, pp. 251-260 (1996).		
	Fiekowsky, P., et al., "Defect Printability Measurement on the KLA-351: Correlation to Defect Sizing Using the AVI Metrology System", SPIE 19th Annual BACUS Symposium on Photomask Technology and Management Conference, pp. 1-6, September 1999.		
	Tejnil, E., et al., "Option for At-Wavelength Inspection of Patterned Extreme Ultraviolet Lithography Masks", SPIE Bacus '99, pp. 1-12 (1999).		
	Hemar, S., et al., "Finding Killer CD Variations by Full-Reticle CD Mapping", Microlithography World, pp. 4, 6, 8 & 10 (Summer 2000).		

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